

AMENDED CLAIMS					
	NO. OF CLAIMS	HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	ADDT'L FEE
Total Claims	22	MINUS 21 =	1	x \$18.00 (103) =	18.00
Independent Claims	4	MINUS 3 =	1	x \$78.00 (102) =	78.00
If Amendment adds multiple dependent claims, add \$260.00 (104)					
Total Amendment Fee					96.00
If small entity status is claimed, subtract 50% of Total Amendment Fee					
TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT					96.00

☐ A claim fee in the amount of \$_____ is enclosed.
☒ Charge \$ 96.00 to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

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Date: November 24, 1999

1768

Patent
Attorney's Docket No. 15290-238

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Jeffrey HUNG et al.

Application No.: 09/002,007

Filed: December 31, 1997

For: ETCHING PROCESS FOR ORGANIC
ANTI-REFLECTIVE COATING



Group Art Unit: 1765

Examiner: L. Vinh

AMENDMENT/REPLY TRANSMITTAL LETTER

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

☐ A Petition for Extension of Time is also enclosed.

☐ Also enclosed is _____

☐ _____ statement(s) claiming small entity status
☐ are also enclosed ☐ were submitted previously.

☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a)
(146/246) is also enclosed.

☐ No additional claim fee is required.

☒ An additional claim fee is required, and is calculated as shown below:

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NOV 30 1999
TC 1700 MAIL ROOM

#10/B

Patent
Attorney's Docket No. 015290-238

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Jeffrey HUNG et al.

Application No.: 09/002,007

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For: ETCHING PROCESS FOR ORGANIC
ANTI-REFLECTIVE COATING



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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Official Action dated August 25, 1999, please amend the above-identified application as follows.

IN THE CLAIMS:

Please amend Claims 1, 6, 11 and 14 and add new Claim 22 as follows:

Claim 1, line 1, change "layer" to --layer,--.

Claim 6, line 3, change "photo etching" to --exposure--.

Claim 11, line 2, change "circuit" to --circuit,--.

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1C-1700 MAIL ROOM

B1 14. (Twice Amended) The oxygen-free [plasma etching gas formulation] system of etching agents of Claim 1, [consisting] wherein the system of etching agents consists

11/26/1999 CVDRACHA 00000078 024800 09002007

01 FC:103 18.00 CH
02 FC:102 78.00 CH